

Joint International Conference on The 8th ICMAP & The 9th ISFM

January 17-20, 2021 | Online Conference

[WB1] Plasma Diagnostics and Process Monitoring Technology II	
Date / Time	January 20 (Wed.), 2021 / 09:00-10:10
Place	Channel B
Session Chair(s)	Se Youn Moon (Jeonbuk Nat'l Univ., Korea)

[WB1-1] Invited

09:00-09:30

Solutions to the Challenges of Quantitative Neutral Species Measurements in Process Plasmas

Jianping Zhao¹, Peter Ventzek¹, Charles Schlechte¹, John Carroll¹, Michael Hummel¹, Toshihiko Iwao², and Kiyotaka Ishibashi²

¹TEL, USA, ²TEL, Japan

[WB1-2]

09:30-09:50

Investigation of Power Coupling Property in E-H Mode Integrated Inductively Coupled Plasmas

Haneul Lee, Ingyu Lee, Sung Hyun Son, Jaemin Song, and Gon-Ho Kim

Seoul Nat'l Univ., Korea

[WB1-3]

09:50-10:10

Computational Analyses of TEOS-Based Plasma Characteristics to Clarify SiO₂ Deposition Mechanisms in PECVD Processes

Hu Li and Kazuki Denpoh

Tokyo Electron Tech. Solutions, Japan